Resource Summary Report

Generated by dkNET on Aug 23, 2026

JEOL: JBX-3050MV Electron Beam Lithography System

RRID:SCR_020166
Type: Tool

Proper Citation

JEOL: JBX-3050MV Electron Beam Lithography System (RRID:SCR_020166)

Resource Information

URL: https://www.jeolusa.com/PRODUCTS/Photomask-Direct-Write-Lithography/Electron-Beam-Lithography/JBX-3050MV

Proper Citation: JEOL: JBX-3050MV Electron Beam Lithography System (RRID:SCR_020166)

Description: Electron beam lithography system for mask reticle fabrication that meets design rule of 45 to 32 nm and pattern writing with high speed, high accuracy and high reliability, achieved by high end technology

Resource Type: instrument resource

Keywords: Jeol, JEOL, Electron Beam Lithography System, Instrument Equipment, USEDit,

Availability: Commercially available

Resource Name: JEOL: JBX-3050MV Electron Beam Lithography System

Resource ID: SCR_020166

Alternate IDs: Model_Number_JBX-3050MV

Record Creation Time: 20220129T080349+0000

Record Last Update: 20260815T182633+0000

Ratings and Alerts

No rating or validation information has been found for JEOL: JBX-3050MV Electron Beam Lithography System.

No alerts have been found for JEOL: JBX-3050MV Electron Beam Lithography System.

Data and Source Information

Source: SciCrunch Registry

Usage and Citation Metrics

We have not found any literature mentions for this resource.